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Attorney Docket No.: SON-2769

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Patent Application of

Hidetoshi OHNUMA, *et al*

Group: 1756

Serial No. 10/603,689

Examiner: Daborah Chacko Davis

Filed: June 26, 2003

Confirmation No. 2872

For: EXPOSURE METHOD, MASK
FABRICATION METHOD, FABRICATION
METHOD OF SEMICONDUCTOR DEVICE
AND EXPOSURE APPARATUS

SUPPLEMENTAL RESPONSE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

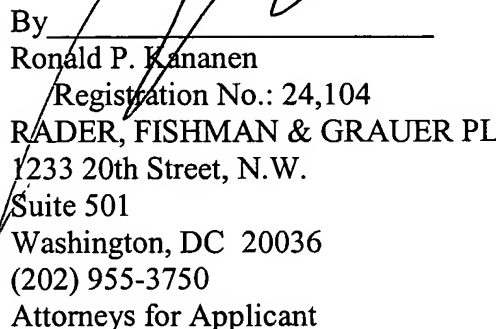
Dear Sir:

Supplementing the Amendment for Response to Office Action mailed February 13, 2006, a certified translation of the priority document is provided. The priority document is JP Application No. 2002-189086, filed on June 28, 2002.

Please consider the Applicant's prior remarks in light of this submission.

Dated: July 3, 2006

Respectfully submitted,

By 

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